

ABSTRACT OF THE DISCLOSURE

Provided is a method of manufacturing a microlens substrate capable of facilitating optical axis alignment and simplifying manufacturing processes by patterning a lens shape of a second microlens array using a first microlens array. The lens shape of the cylindrical second microlens array is patterned by irradiating the first microlens array with ultraviolet rays. Light emitted from a linear light source which is variable in its position is imaged on a focal surface of the first microlens array by a collimator lens and the first microlens array, and a resist layer formed by being coated on the focal surface is exposed. By performing exposure while changing the position of the linear light source, a resist pattern of a desired cylindrical shape can be obtained. Thereafter, etching is performed to transfer the shape of the resist pattern onto an intermediate glass layer, and recesses are buried with a high refractive index UV curable resin.